WEST Search History

Hide Items	Restore	Clear	Cancel
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DATE: Saturday, May 01, 2004

Hide?	<u>Set</u> <u>Name</u>	Query	<u>Hit</u> Count	
DB=USPT; PLUR=YES; OP=ADJ				
	L34	etch\$3 and 6369887.pn.	1	
	L33	resist and 6369887.pn.	1	
	L32	115 and 6369887.pn.	0	
	L31	resist and 5940175.pn.	0	
	L30	115 and 5940175.pn.	0	
	L29	resist and 6015718.pn.	0	
	L28	115 and 6015718.pn.	0	
	L27	etch\$3 and 5963315.pn.	0	
	L26	etching and 5963315.pn.	0	
	L25	118 and 5963315.pn.	0	
	L24	117 and L23	0	
	L23	115 and 5963315.pn.	1	
	L22	115 and 6660528.pn.	0	
	L21	('6699399' '6136211')!.PN.	2	
	L20	L19 and l17	59	
1000	L19	114 and 115 and 116 and 118	67	
	L18	etching chamber or etching machine	2596	
	L17	silicon oxide or silicon nitride or silicon oxynitride or polysilicon	101976	
	L16	wafer	116440	
	L15	photoresist	60050	
	L14	(count\$3 or measur\$3) with (particulate or particle or (dynamic particle))	43015	
DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ				
	L13	11 and 12 and 112	1	
	L12	etching chamber or etching machine	2522	
	L11	L10 and 14	1	
	L10	19 and 12 and 13	9	
	L9	(monitor\$3 or indicat\$3 or determin\$6) with (contamination or pollut\$3 or particle)	16954	
	DB=PGPB; PLUR=YES; OP=ADJ			
	L8	US-20030073247-A1.did.	1	

L7	US-20030073247-A1.did.	1
DB=EB	PAB,JPAB,DWPI; PLUR=YES; OP=ADJ	
L6	14 and L5	1
L5	11 and 12 and 13	13
L4	silicon oxide or silicon nitride or silicon oxynitride or polysilicon	92208
L3	wafer	185662
L2	photoresist	51059
L1	(count\$3 or measur\$3) with (particulate or particle or (dynamic particle))	20963

END OF SEARCH HISTORY